



MEXT (Ministry of Education, Culture, Sports, Science and Technology)
Program for Fostering Regional Innovation (Global Type)
-Tokai Region Nanotechnology Manufacturing Cluster-



4th International Symposium on Advanced Plasma Science
and its Applications for Nitrides and Nanomaterials

ISPlasma2012

March 4-8, 2012
Chubu University, Aichi, Japan

Chairperson : Masaru Hori, Plasma Nanotechnology Research Center, Nagoya University
Vice-Chairperson : Hideki Masuda, Nagoya Institute of Technology
Hiroshi Amano, Nagoya University
Mineo Hiramatsu, Meijo University

Related Fields

- PLASMA SCIENCE**
- Plasma Source
 - Flexible Electronics
 - Advanced Plasma Measuring Technology
 - Plasma Biology and Medicine
 - Modeling and Simulation
 - Plasma for Clean Energy
 - Etching Process
 - Plasma for Nanotechnology
 - Thin Film Deposition Process
- NITRIDE SEMICONDUCTORS**
- Crystal Growth of GaN and Related Materials
 - MBE Growth of Nitrides
 - Characterization
 - Device Processing
 - Optical Devices
 - Electronic Devices
- NANOMATERIALS**
- Nanocarbon Materials
 - Nanoparticle/Nanowire/Nanorod
 - Porous Materials
 - Nanomaterials for Energy Applications
 - Surface Modification/ Surface Functionalization
 - Composite/ Functionally Grade Materials

Abstract Submission : Mon, Oct 24, 2011 (11:00 AM Japan Time)

Special Issue

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP).
Instruction for submitting papers will be informed by late December.

Exhibition

During the symposium, enterprises and related organizations will exhibit at the venue.

Registration

Advanced Online Registration is required.

	General	Student
Registration Fee : Early Registration (Before Jan 31, 2012)	JPY 20,000	JPY 3,000
Late Registration (Until Feb 23, 2012)	JPY 25,000	JPY 5,000
On-site Registration	JPY 30,000	JPY 7,000
Banquet Fee (on Mar 6, 2012)	JPY 5,000	JPY 2,000

* Refunds cannot be made at any reason.

Those attending only the Industry-Academia-Government Collab. Session on Mar 6, PM : Registration Fee is FREE.

Speakers

Plenary Speaker Atsuo Iiyoshi (Chubu University, JAPAN)

Keynote Speakers

B. Daudin (CEA-Grenoble, FRANCE)
M. Meyyappan (NASA Ames Research Center, USA)
T. Palacios (Massachusetts Institute of Technology, USA)

T. Degawa (TECHNO INTEGRATION Co. Ltd, JAPAN)
Y. Nanishi (Ritsumeikan Univ., JAPAN/Seoul National Univ., KOREA)
J. Speck (University of California Santa Barbara, USA)

P. Kamat (University of Notre Dame, USA)
R. Nemanich (Arizona State University, USA)

Invited Speakers

Y. Awano (Keio University, JAPAN)
P. Favia (University of Bari, ITALY)
M. Hasegawa (AIST, JAPAN)
S. Inagaki (Toyota Central R&D Labs., Inc., JAPAN)
K. Kishino (Sophia University, JAPAN)
H. Nishihara (Tohoku University, JAPAN)
W. Saito (Toshiba Corporation, JAPAN)
V. Svrcek (AIST, JAPAN)

R. P. Brinkmann (Ruhr-University Bochum, GERMANY)
M. Goeckner (University of Texas at Dallas, USA)
T. Hashimoto (SixPoint Materials, Inc., USA)
A. Ito (National Institute for Fusion Science, JAPAN)
X. Li (Peking University, CHINA)
T. Nozaki (Tokyo Institute of Technology, JAPAN)
H. Shea (EPFL, SWITZERLAND)
A. Yoshikawa (Chiba University, JAPAN)

K. Chen (The Hong Kong University of Science and Technology, CHINA)
H. Yamaguchi Greenslet (University of Florida, USA)
T. Hashizume (Hokkaido University, JAPAN)
T. Kaneko (Tohoku University, JAPAN)
P. Mayrhofer (Montanuniversitaet Leoben, AUSTRIA)
G. Oehrlin (University of Maryland College Park, USA)
J. Suda (Kyoto University, JAPAN)

Tutorial Speakers

H. Amano (Nagoya University, JAPAN)
M. Hiramatsu (Meijo University, JAPAN)

U. Czarnetzki (Ruhr-University Bochum, GERMANY)
A. Khan (University of South Carolina, USA)

J. G. Han (Sungkyunkwan University, KOREA)
A. Kono (Nagoya University, JAPAN)

Tutorial

Tutorial for Plasma Science, Nitride Semiconductors and Nanomaterials will be held on Sun, Mar 4, PM.

Focused Sessions

Focused Sessions will be held in the following themes. Green Innovation/Nitride and Plasma Collaboration/ Advanced Carbon Materials/Industry-Academia-Government Collaboration

Panel Discussion

Establishment of Advanced Plasma Nanotechnology Science Foundation toward Sustainable Development (Mar. 6)

<Moderator> N. Odake (Nagoya Institute of Technology, JAPAN) *Those attending only this Session : Registration Fee is FREE.

Application of Advanced Plasma Technology for Nitride Semiconductors III

-Importance and problem of plasma processing in nitride semiconductor devices- (Mar. 7)

<Moderator> H. Amano (Nagoya University, JAPAN)

Advanced Plasma Nanotechnology towards Green Innovation (Mar. 8)

<Moderator> T. Nozaki (Tokyo Institute of Technology, JAPAN)

*Program and speakers listed above may change. *Listed in alphabetical order.

Sponsored by : Aichi Science & Technology Foundation, ISPlasma2012 Organizing Committee

Co-sponsored by : Aichi Prefecture, Nagoya City, Gifu Prefecture, Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University, The Japan Society of Applied Physics, The Japan Society of Plasma Science and Nuclear Fusion Research, The Japanese Association for Crystal Growth

Contact

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